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(54) FULLERENE-CONTAINING SENSITIVE MATERIAL, RESIST AND PATTERN FORMING METHOD USING SAME

(57)Abstract:

PROBLEM TO BE SOLVED: To prevent the deterioration of the resist shape after exposure due to impurities in air by using a sensitive material comprising a substance having amino groups and a fullerene.

SOLUTION: The sensitive material comprises a substance having amino groups and a fullerene or its derivative. The substance having amino groups is a polyaniline or its derivative. The fullerene or its derivative is not particularly limited but C60 or its derivative having high reactivity with amino groups is preferably used. A polyaniline is desirably used as the substance having amino groups and a polyaniline having any unit cell such as aniline or aniline having a substituent may be used but a poly(o-alkylaniline) or a poly(o-alkoxyaniline) is preferably used in consideration of solubility to a solvent. The alkyl group in the poly(o-alkylaniline) has 1-24, more preferably 1-12 carbon atoms.



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